WHAT IS CLAIMED IS:

- 3. The method of Claim 1, said fabricating comprising fabricating at least two micromirror devices on said substrate.
- 4. The method of Claim 1, said fabricating comprising fabricating at least two micromirror devices on a semiconductor substrate.
- 5. The method of Claim 1, said fabricating comprising fabricating at least two micromirror arrays on said substrate.
- 6. The method of Claim 1, said fabricating comprising fabricating at least two micromirror arrays on a semiconductor substrate.
- 7. The method of Claim 1, said overcoating with a protective layer comprising overcoating with a plastic layer.
- 8. The method of Claim 1, said overcoating with a protective layer comprising overcoating with a polymer resin.
 - 9. The method of Claim 1, said overcoating with a protective layer comprising overcoating with a PARYLENE layer.

- 10. The method of Claim 1, said overcoating with a protective layer comprising overcoating with a acrylate monomer layer.
- 11. The method of Claim 1, said overcoating with a protective layer comprising overcoating with a acrylate oligomer layer.
- 12. The method of Claim 1, said overcoating with a protective layer comprising applying a protective overcoat by vapor deposition.
- 13. The method of Claim 1, said overcoating with a protective layer comprising applying a protective overcoat by immersing said substrate in a liquid protective overcoat material.
- 14. The method of Claim 1, said overcoating with a protective layer comprising applying a protective overcoat by spinning-on a protective overcoat layer.
- 15. The method of Claim 1, comprising:

thermally curing said protective layer.

16. The method of Claim 1, comprising:

curing said protective layer using ultraviolet light.

- 17. The method of Claim 1, said overcoating with a brittle layer comprising overcoating with a photoresist layer.
- 18. The method of Claim 1, said overcoating with a brittle layer comprising overcoating with a photoresist layer, further comprising:

baking said photoresist layer.

19. The method of Claim 1, said overcoating with a brittle layer comprising overcoating with a photoresist layer, further comprising:

deep UV hardening said photoresist layer.

- 20. The method of Claim 1, said overcoating with a brittle layer comprising overcoating with a brittle layer to prevent said protective layer from delaminating from said substrate.
- 21. The method of Claim 1, said sawing comprising sawing through said protective and overcoat layers.
- 22. The method of Claim 1, said sawing comprising sawing through said protective and overcoat layers and said substrate to separate said micromechanical devices.
- 23. The method of Claim 1, said sawing comprising sawing through said protective and overcoat layers and partially through said substrate layer.